



III-V/III-N Materials and Devices

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Message from the Guest Editor

Dear Colleagues,

III-V/III-N compound semiconductors have attracted much attention owing to their superior electrical and photonic properties for devices. The III-V/III-N-based devices have been applied to practical applications in solid-state photonics and electronics. Furthermore, several researchers have modulated the compound semiconductor structures, enhancing the electrical, optical, and thermal properties for novel and/or improved performance in applied technologies. This Special Issue focuses on the latest research results for III-V materials/devices, III-N materials/devices, and their applications such as electronics, sensors, photonics, and photovoltaics.

The topics of interest include but are not limited to:

- Theory of III-V/III-N materials;
- Growth of III-V/III-N materials;
- Characterization of III-V/III-N materials;
- III-V/III-N material-based devices (electronics, sensors, photonics, and photovoltaics, etc.).





Editor-in-Chief

Message from the Editor-in-Chief

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